

### IN THE ABSTRACT

Please substitute the abstract presented with the following. A marked-up copy of the abstract, showing the changes made thereto, is attached in Appendix A.

-- A substrate attracting and holding method includes steps of supporting a substrate by use of a protrusion provided on a holding table for holding the substrate and reducing pressure between the holding table and the substrate to attract and hold the substrate. The protrusion is disposed to be placed in a predetermined positional relation, with respect to a direction along the surface of the substrate, with (i) a position of an alignment mark to be used for processing the substrate or (ii) a position to with respect to which an alignment mark is to be produced. --

### IN THE SPECIFICATION:

Please amend the specification as follows:

Please substitute the paragraph beginning at page 1, line 5, with the following. A marked-up copy of this paragraph, showing the changes made thereto, is attached in Appendix A.

-- This invention relates to a substrate attracting and holding system for grasping a substrate or workpiece and, more particularly, to a substrate attracting and holding system for use in a semiconductor manufacturing apparatus, a liquid crystal substrate manufacturing apparatus, a magnetic head manufacturing apparatus, a semiconductor inspection apparatus, a liquid crystal inspection apparatus, or a magnetic head inspection apparatus or for use in the manufacture of a